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	APPLICANT Hans Wilfried Peter KOOPS	
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U. S. PATENT DOCUMENTS

EXAMINER INITIAL	PATENT NUMBER	PATENT DATE	NAME	CLASS	SUBCLASS	FILING DATE
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FOREIGN PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
						YES	NO
	196 16 324*	October 30, 1997	Germany				
	0 614 126*	September 7, 1994	Europe				
	63 249837*	October 17, 1988	Japan				
SA	24 46 789**	September 2, 1976	Germany				
↓	24 60 716**	May 6, 1976	Germany				
	24 60 715**	June 24, 1976	Germany				
↓	25 15 550**	October 7, 1976	Germany				

* Copy of Reference is not enclosed because reference is cited in Search Report (copy of reference provided by International Searching Authority).
 ** Mentioned in the Specification.

OTHER DOCUMENTS

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EXAMINER	Shamim Ahmed	DATE CONSIDERED	7/24/01
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